

# **NEMO5 on Blue Waters - A Flexible Package for Nanoelectronics Modeling Problems**

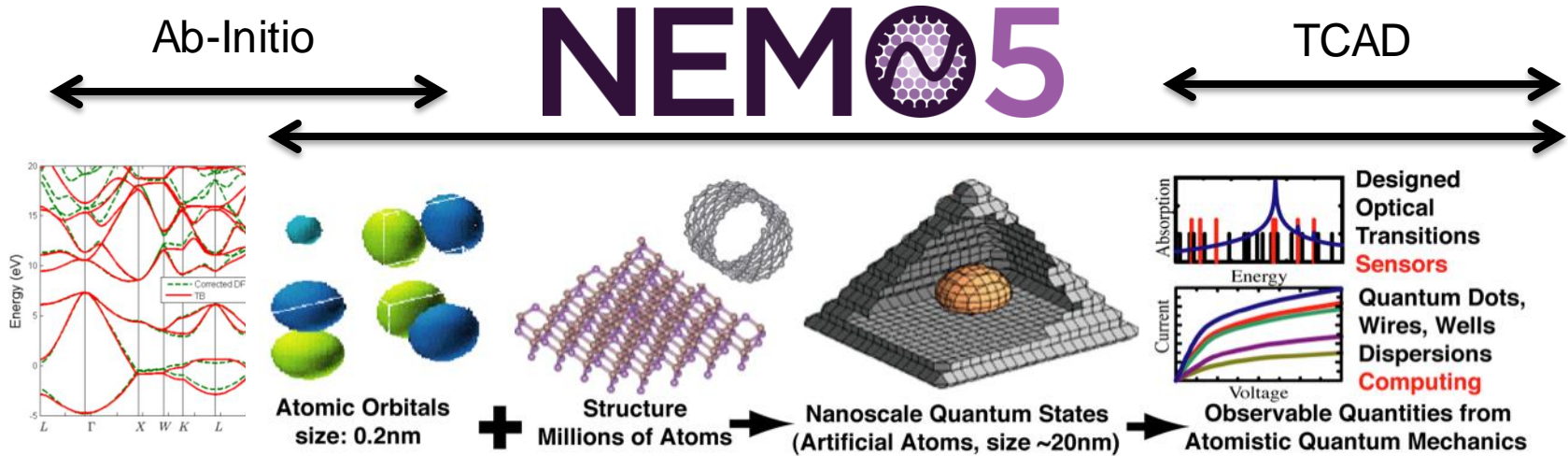
**Jim Fonseca**

**Network for Computational Nanotechnology  
PRAC - Accelerating Nano-scale Transistor  
Innovation**

**PI: Gerhard Klimeck**

**Blue Waters Symposium**

**May 2015**



## Goal:

- Device performance with realistic extent, heterostructures, fields, etc. for new / unknown materials

## Problems:

- Need ab-initio to explore new material properties
- Ab-initio cannot model non-equilibrium.
- TCAD uses quantum corrections

## Approach:

- Ab-initio:
  - Bulk constituents
  - Small ideal superlattices
- Map ab-initio to tight binding (binaries and superlattices)
- Current flow in ideal structures
- Study devices perturbed by:
  - Large applied biases
  - Disorder
  - Phonons

- **Multiscale/multiphysics**

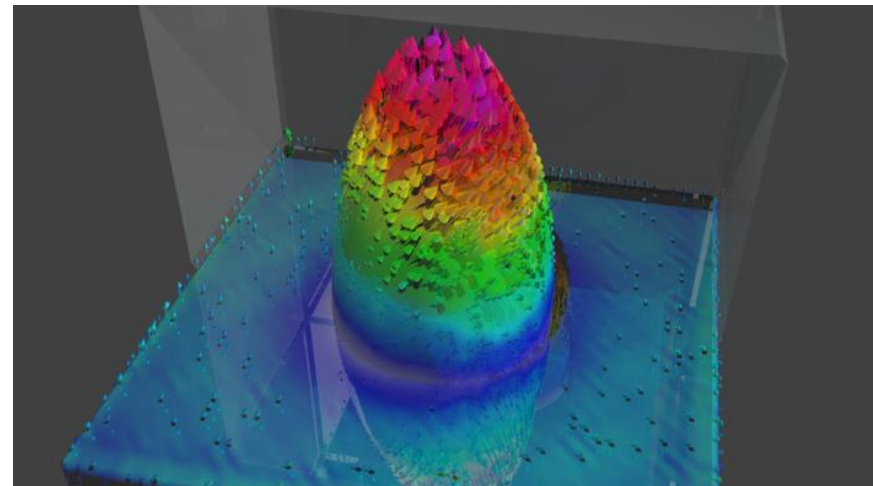
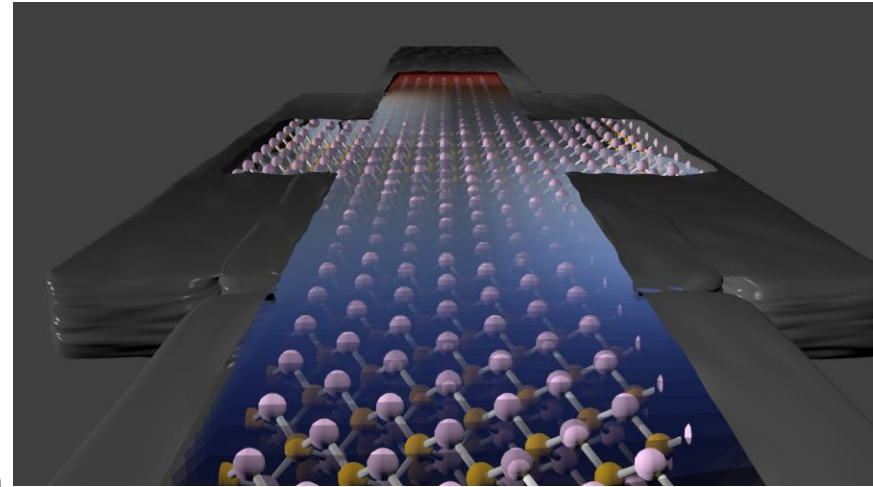
- Empirical tight binding
- NEGF, DD, QTBM, EM
- Electron core, k.p, mode space
- Ohmic and Schottky contacts
- Scattering optical and acoustic
- Phonons
- Strain models-VFF, Keating, Lazarenkova
- External magnetic fields

- **Solves**

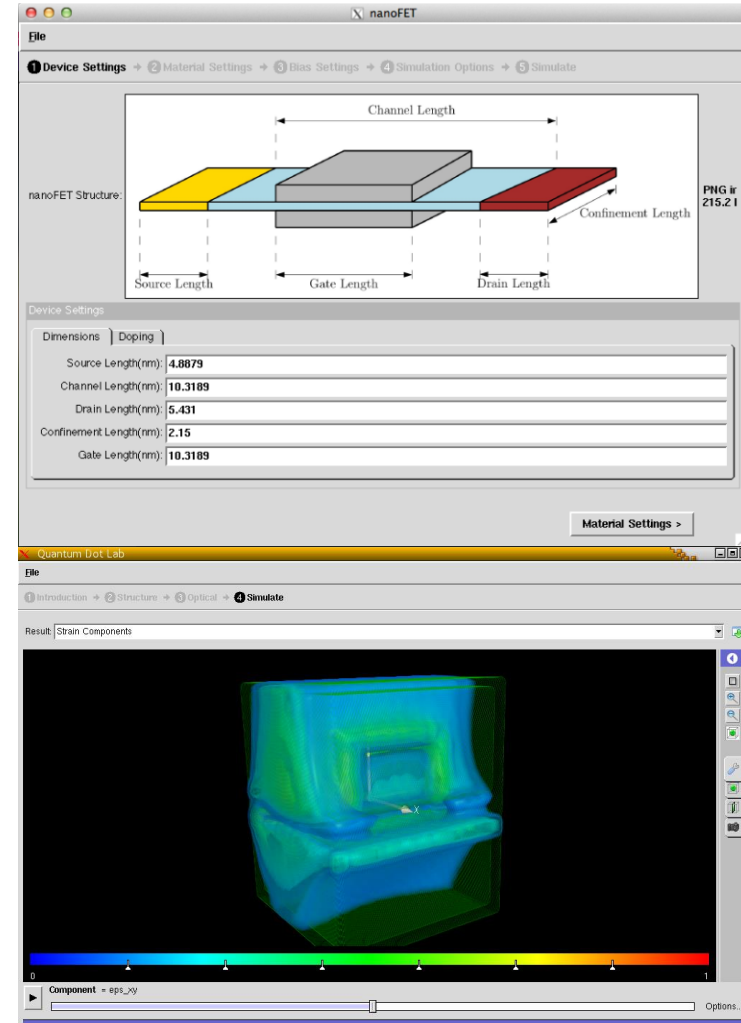
- Atomistic strain
- Electronic band structures
- Charge density
- Potential
- Current

- **4-level MPI parallelization**

- bias, energy, momentum, space



- Distribution and Support Group on nanoHUB.org
  - » <https://nanohub.org/groups/nemo5distribution>
  - » Source code, example, discussion forum, run NEMO5 on Purdue Resources
  
- nanoHUB.org
  - » 330,000 annual users
  - » 4,200 resources (video lectures, presentations, tutorials, etc.)
  - » 330 simulation tools
  - » Nanoelectronics, nanophotonics, materials science, molecular electronics, carbon-based systems, Microelectromechanical systems
  - » 4,200 resources (video lectures, presentations, tutorials, etc.)
  - » NEMO5 Tools
    - ✓ Quantum Dot Lab
    - ✓ Crystal Viewer
    - ✓ Bandstructure Lab



## **Non-equilibrium Green's functions method: Non-trivial and disordered leads**

Yu He, Yu Wang, Tillmann Kubis,  
Gerhard Klimeck



# Problem: assumption of periodic contacts in NEGF contradicts experiment

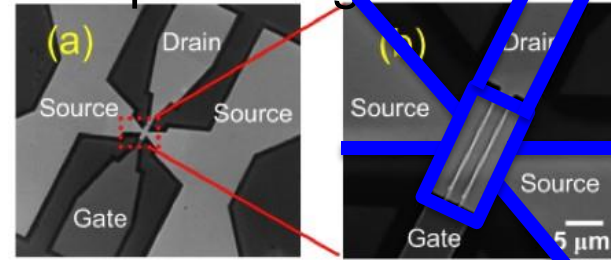
semi-infinite periodic contacts.

Common self-energy methods  
Sancho Rubio,  
transfer matrix

Source

Drain

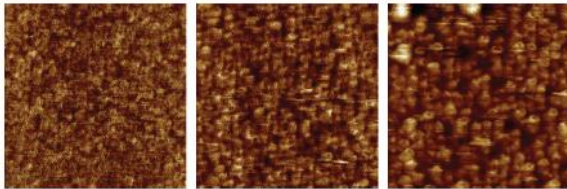
Non-periodic geometries



[http://www.electroiq.com/articles/sst/2010/12/iedm-reflections\\_.html](http://www.electroiq.com/articles/sst/2010/12/iedm-reflections_.html)

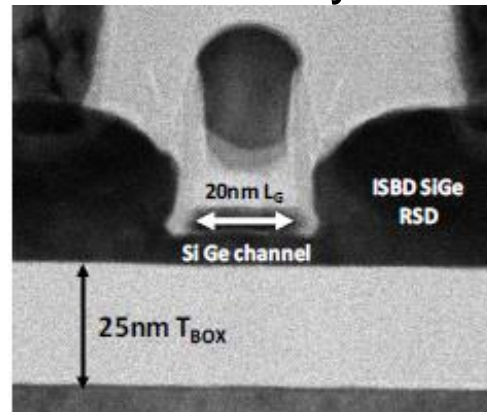
But in the real world...

Roughness



S. Koenig et al, Appl. Phys. Lett, Vol. 104, pp. 103106, 2014

Random alloy



Q. Liu, et al, IEDM p.229 2013

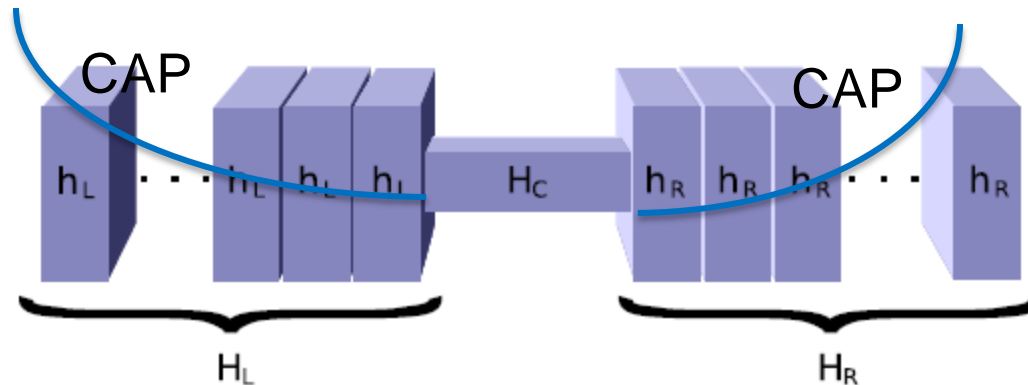
**Periodic assumption contradicts realistic contacts**



How to solve non-periodic contacts?

## Problem:

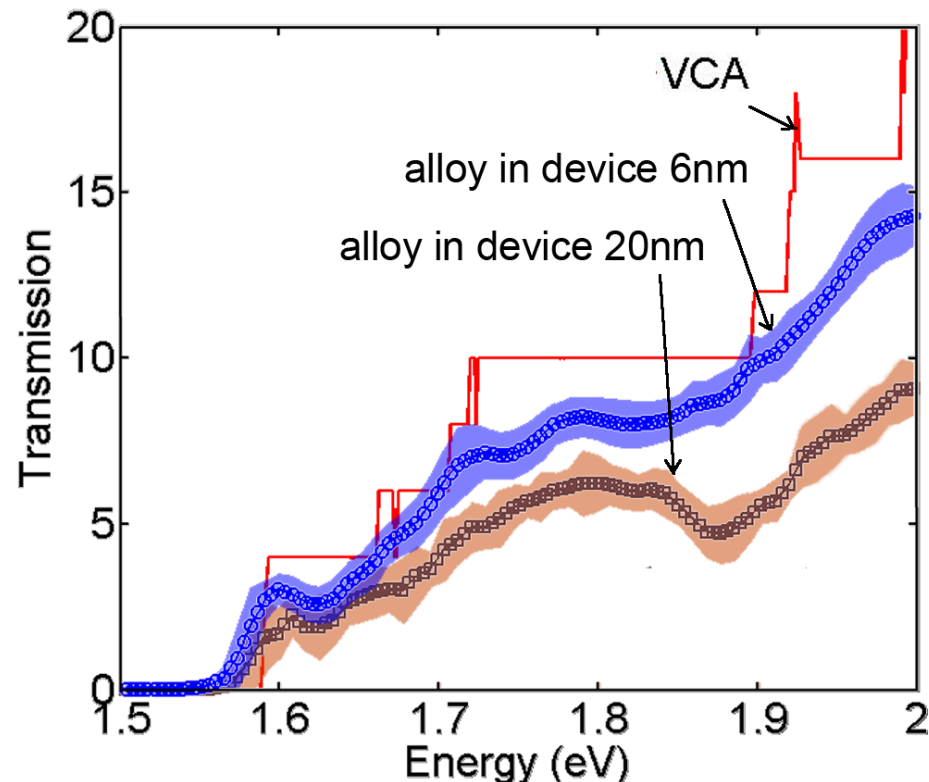
- No exact solution for semi-infinite systems unless periodicity assumed
- Approximate solution
  - ✓ Physically correct
  - ✓ Numerically solvable for arbitrary contact structures



J. Driscoll et al, Phys. Rev. B. Vol. 78, pp. 245118, 2008

## Idea: extend complex absorbing potential (CAP) method

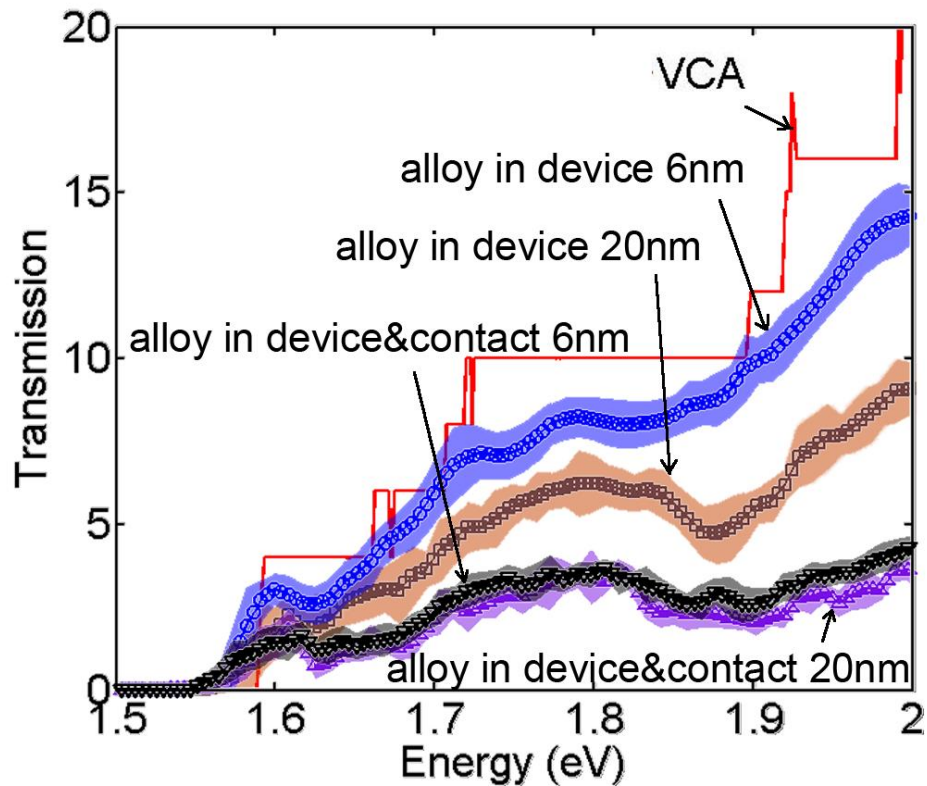
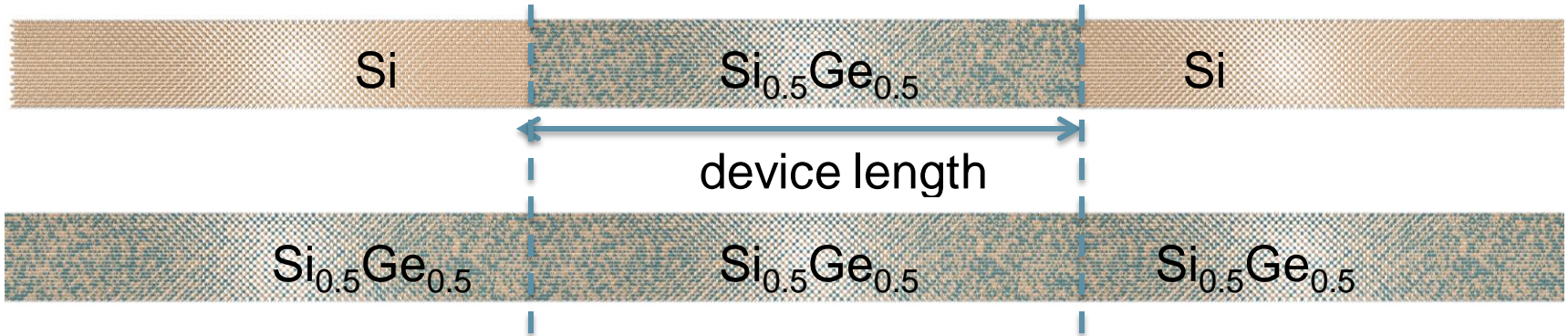
- **Non-periodic contact** : Hamiltonian for explicit contact segments;
- **CAP serves as scattering** : physical assumption of contacts;
- **Efficient, memory thin** : converge within finite iterations;



**Example:**  
 3x3nm  $\text{Si}_{0.5}\text{Ge}_{0.5}$  nanowire in  $\text{sp}^3\text{d}^5\text{s}^*$   
 tight binding  
 Device length 20nm and 6nm  
 Results averaged over 50 samples

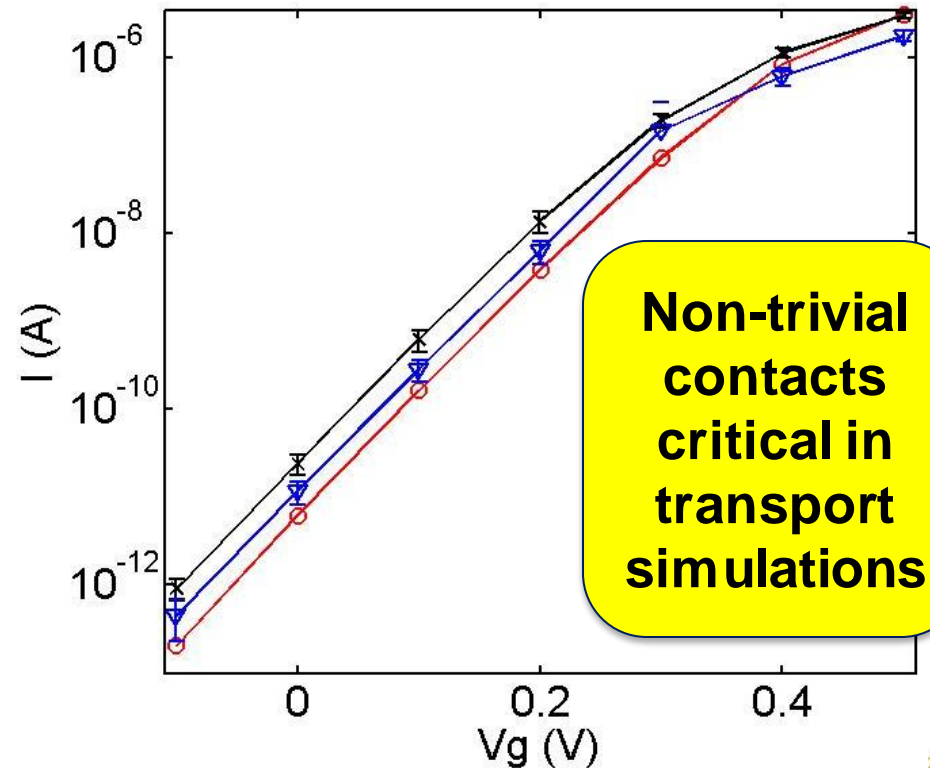
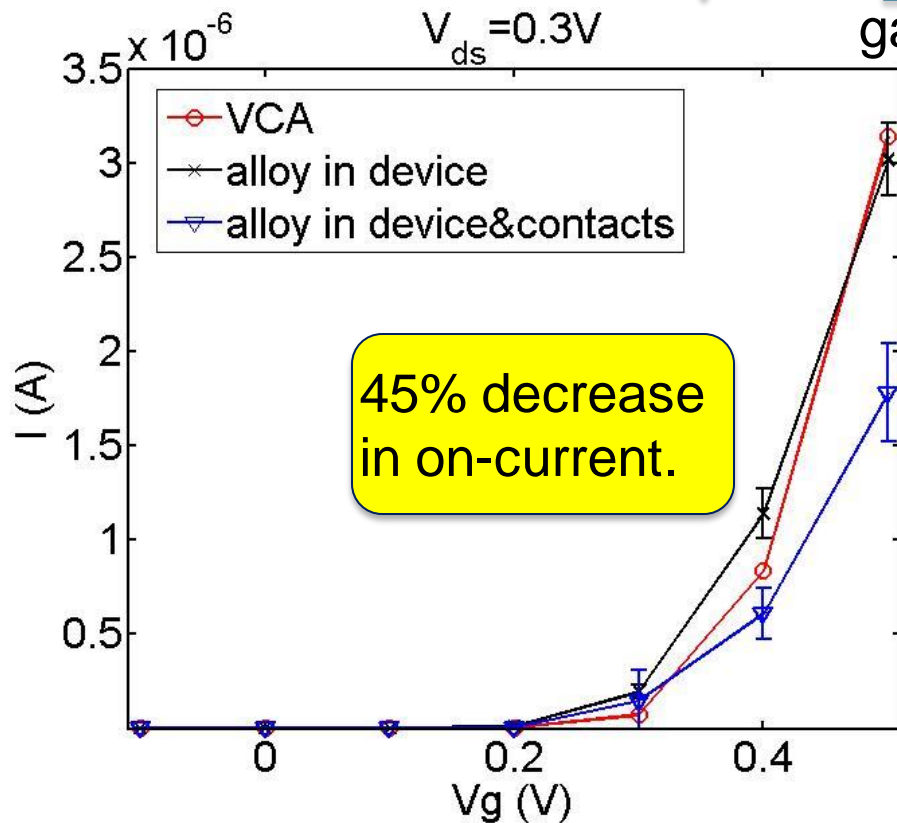
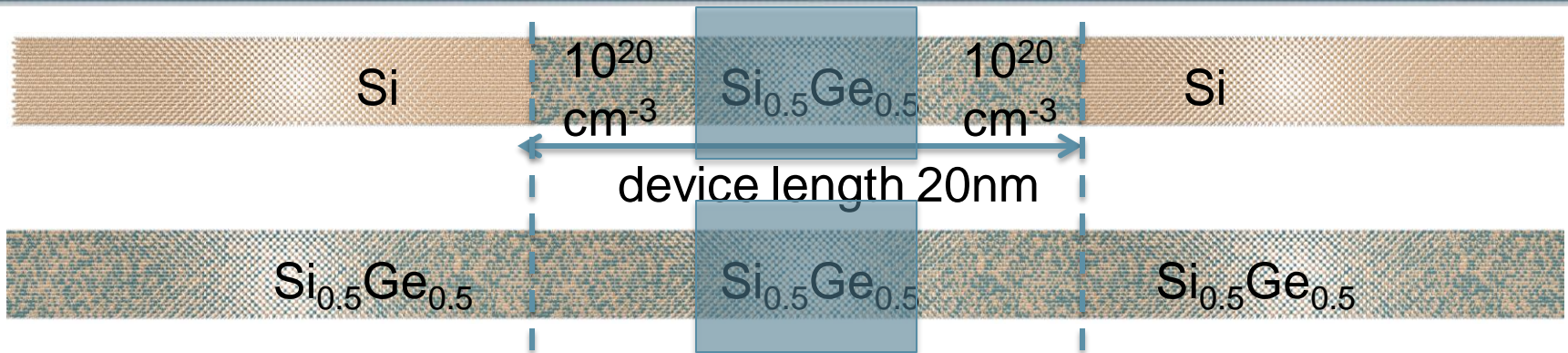
**Justification:**  
 With same effective alloyed disorder in  
 contacts, expected transmission has  
 weak dependence of device length





- ✓ Alloyed contact yield virtually device length independent transmission;
- ✓ DOS of contacts match device better → less reflections of electrons;

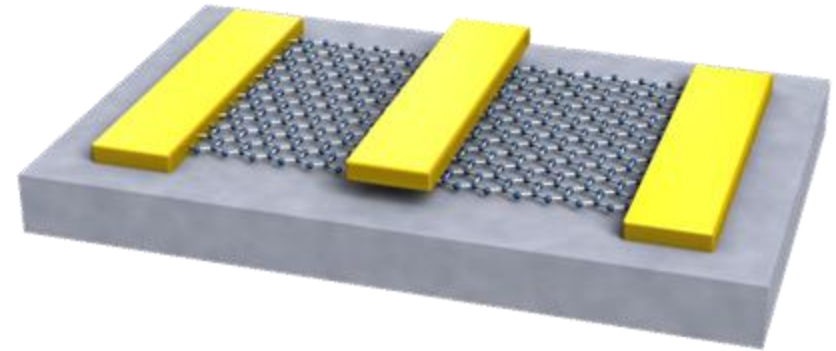
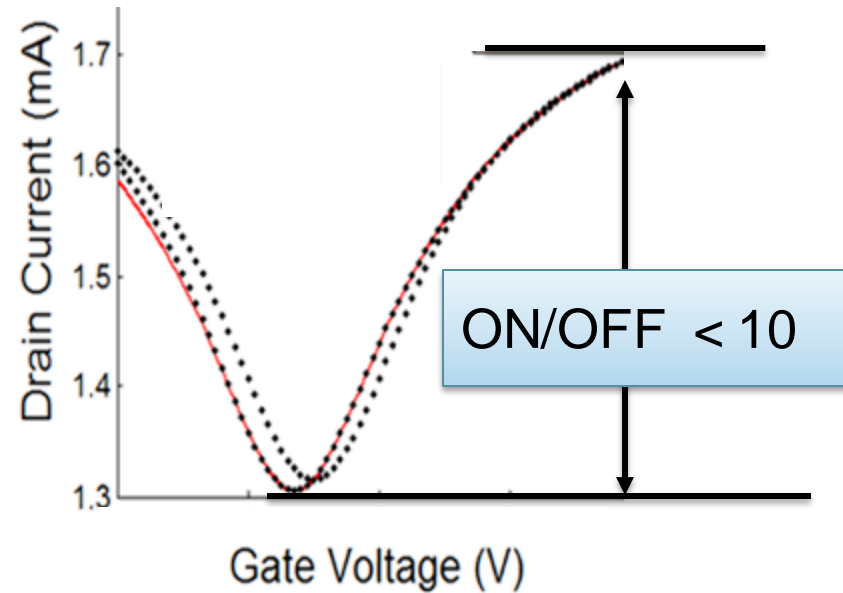
**General lead approach works well for contacts with alloy randomness.**



# **Bilayer Graphene: a Good candidate for Transistors?**

Fan Chen, Hesameddin Ilatikhameneh,  
Rajib Rahman, Gerhard Klimeck





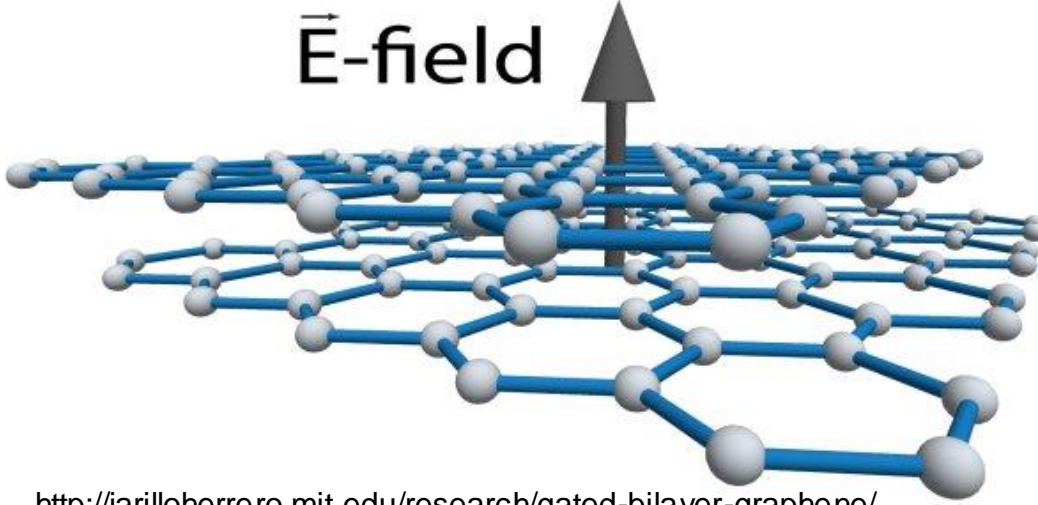
- Graphene has a zero band gap
- It has a good high ON current, but it can't be turned off

## We need to achieve:

- Large ON/OFF ratio needed in transistors ( $\sim 10^5$ )
- Small OFF current  $\rightarrow$  Low power consumption



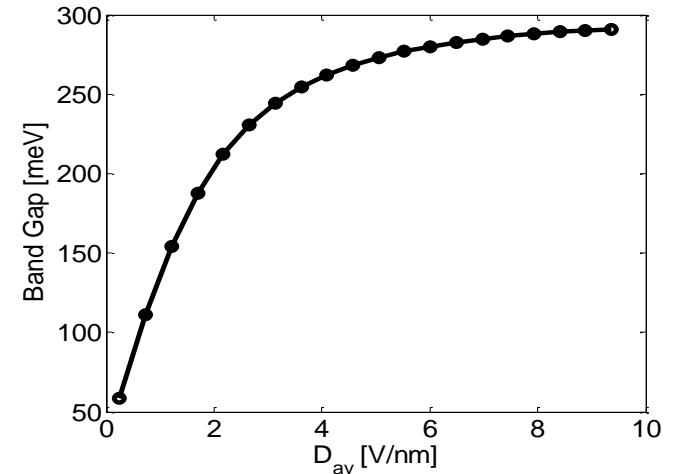
$\vec{E}$ -field 



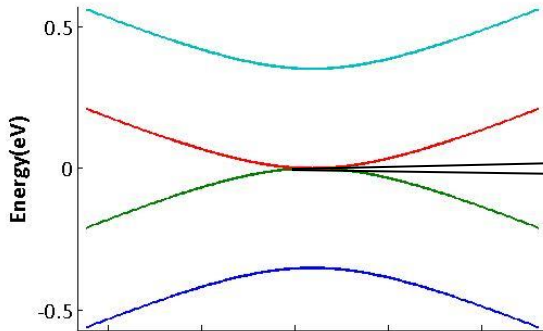
<http://jarilloherrero.mit.edu/research/gated-bilayer-graphene/>

Bandgap vs. E-Field

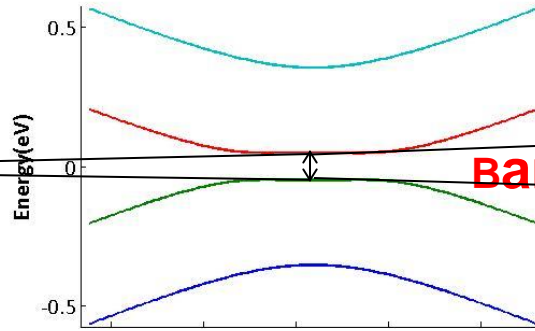
Bilayer Graphene Band Gap with  $D_{av}$



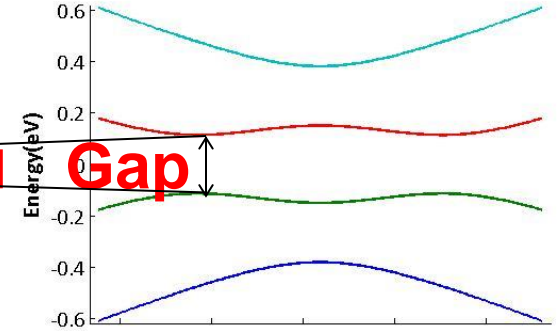
**Bandstructure**



**Small field**



**Large field**



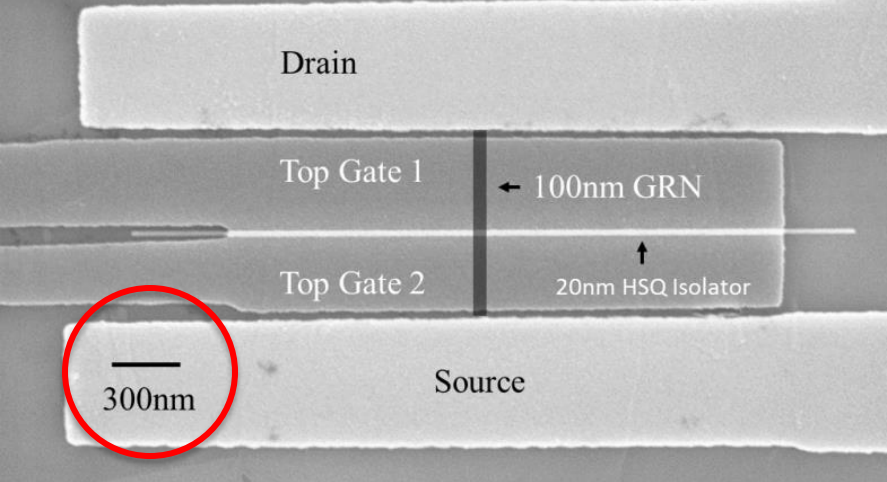
**Band Gap**

**Bilayer Graphene: Create a Band-Gap by Electric Field**

- Control band-gap by applying vertical electric field

Tao. Chu, Prof. Zhihong Chen Purdue

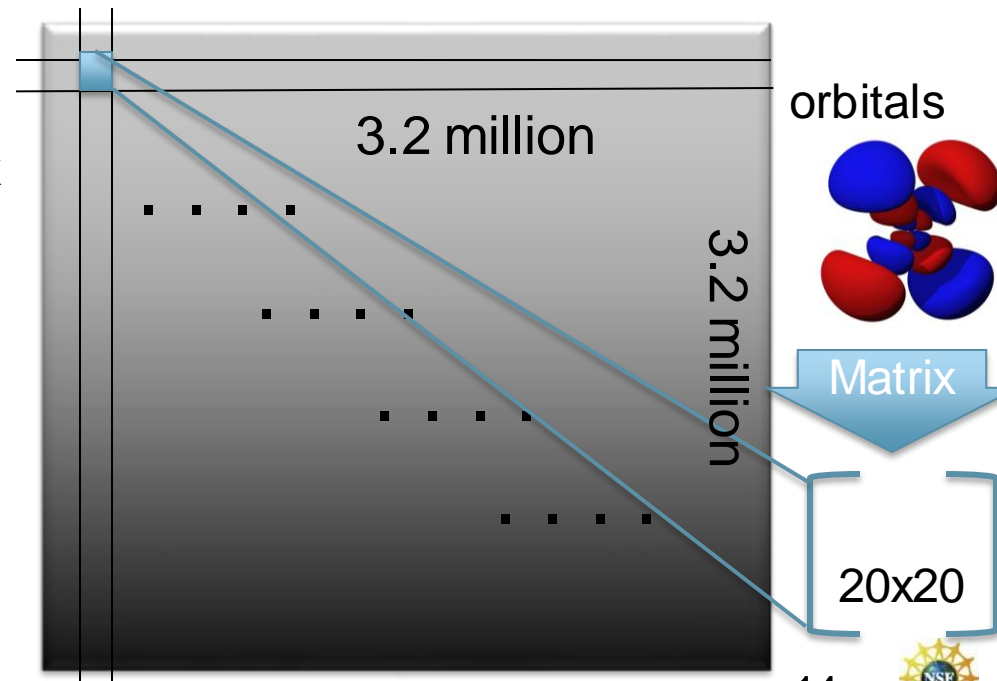
Daniel Mejia

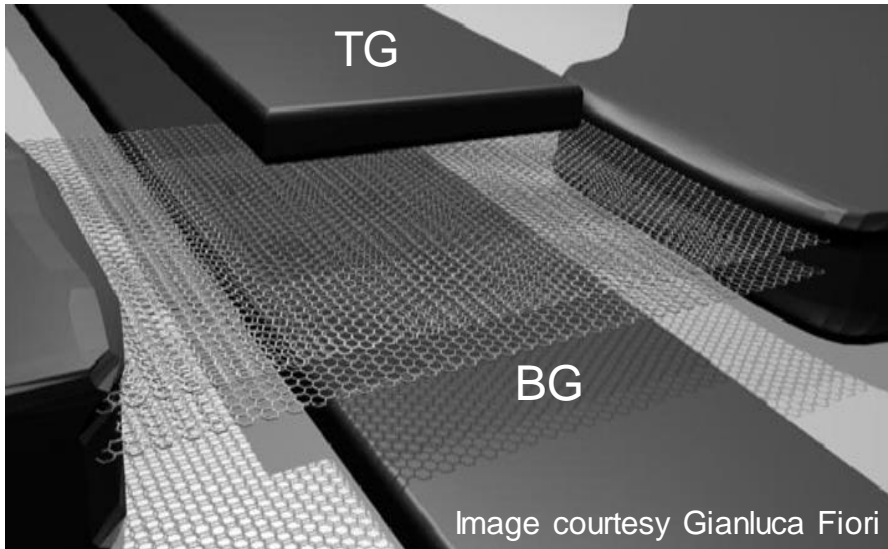


## Challenge:

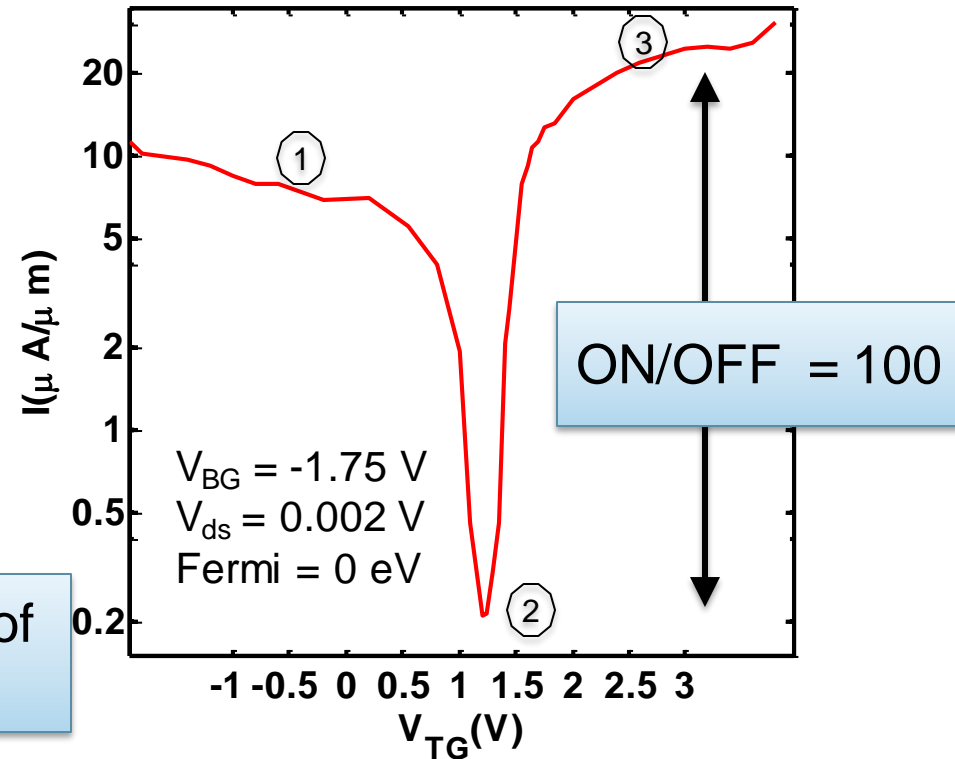
- Matrix size ~ 64 million
- Inverse, Eigenvalues

- ① Limitation from fabrication technique, short channel effect, gate leakage ...
  - ② Device size is typically 100nm (thick) x 200nm (long) x 20nm (wide)
- 3.2 million atoms in simulation





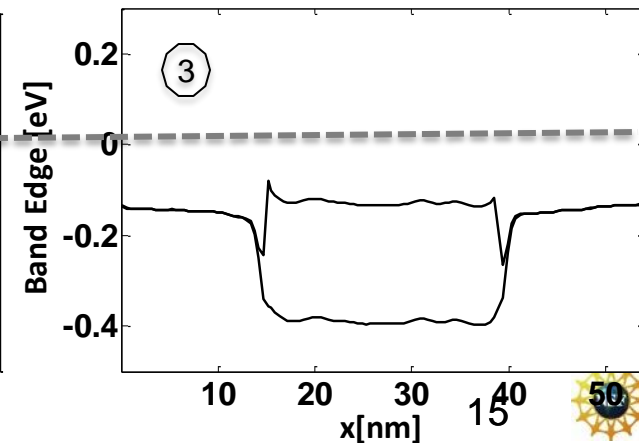
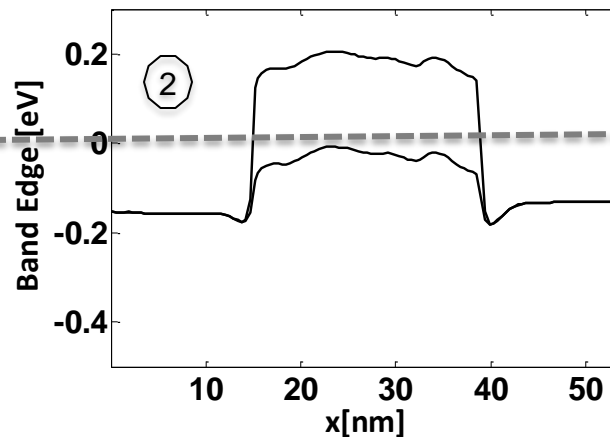
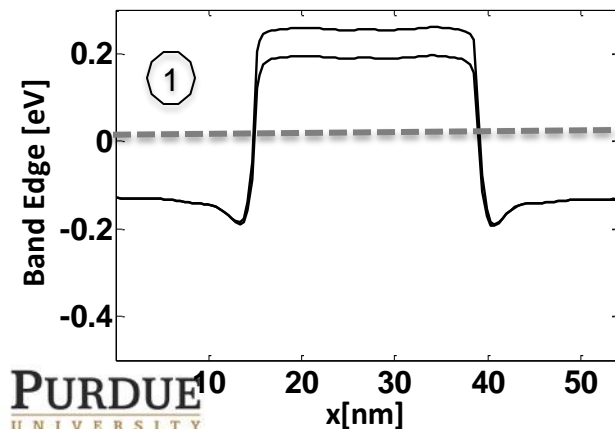
Band Gap opens through the change of Top Gate



$V_{\text{TG}} = -1.4\text{V}$

$V_{\text{TG}} = 1.15\text{V}$

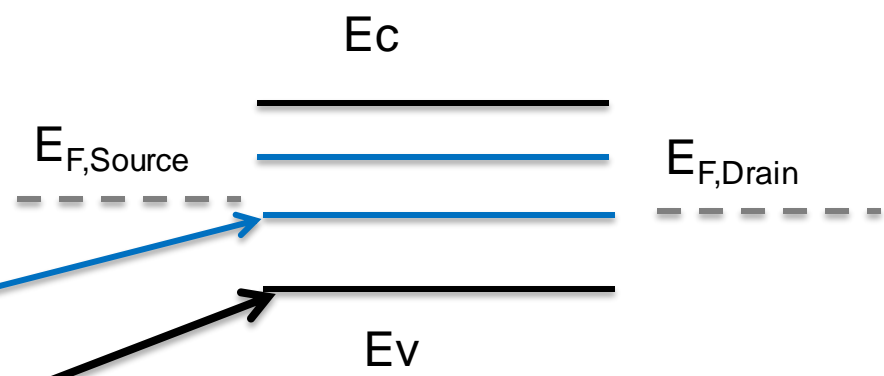
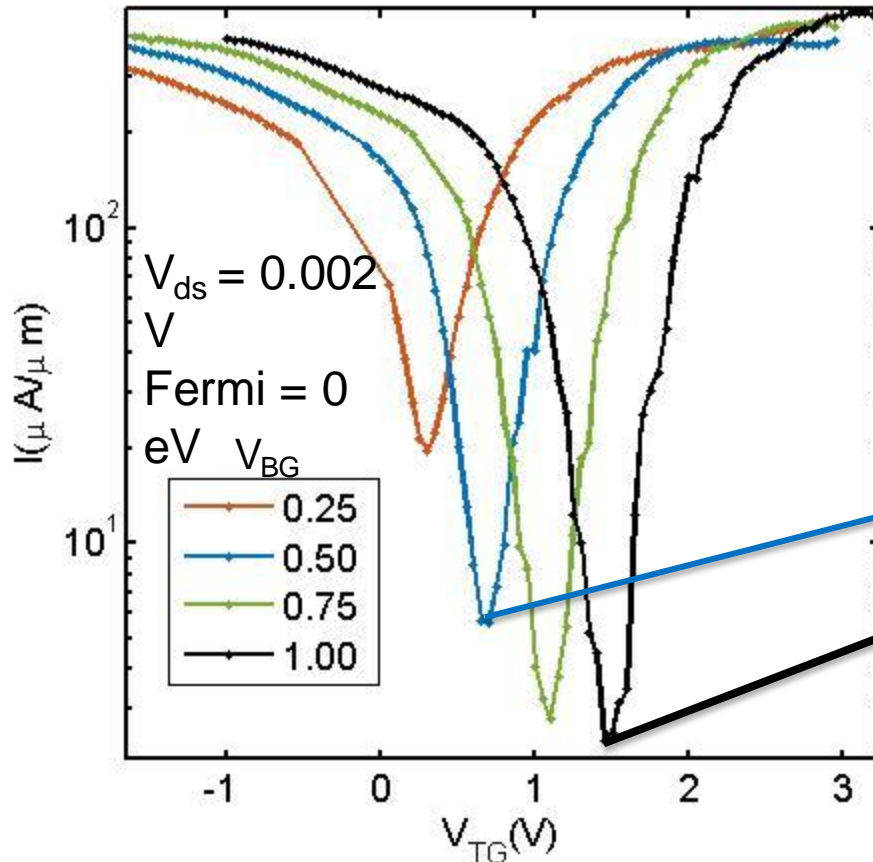
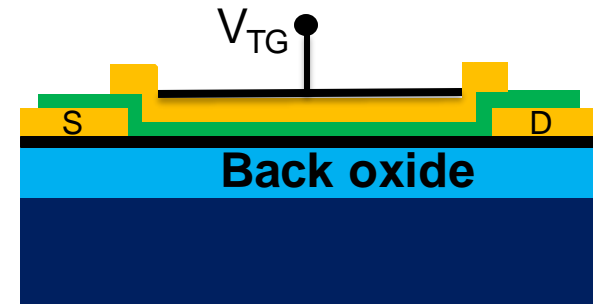
$V_{\text{TG}} = 3.6\text{V}$



Dynamic band gap:

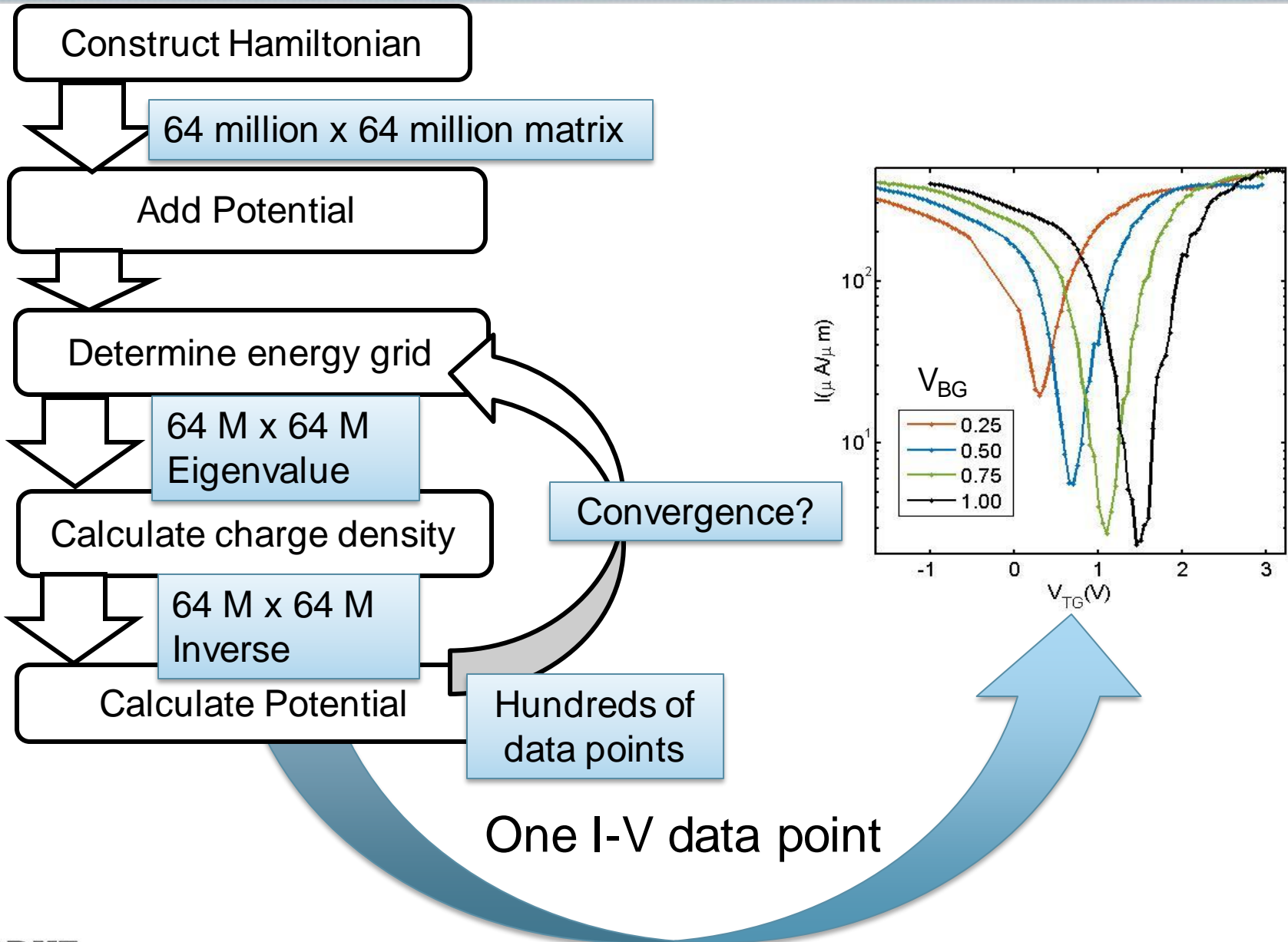
$$|V_{BG}| \uparrow \Rightarrow E \uparrow \Rightarrow E_g \uparrow \Rightarrow I_{ON}/I_{OFF} \uparrow$$

## Physical structure



Band Gap modulated by back gate





# iNEMO

- PI: Gerhard Klimeck
- 3 Research Faculty: Tillmann Kubis, Michael Povolotskyi, Rajib Rahman
- Research Scientist: Jim Fonseca
- 2 Postdocs: Bozidar Novakovic, Jun Huang
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- Ryan Mokos
- Intel, Samsung, Philips, TSMC